## **EAST Search History**

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	5721	(anti\$1reflecti\$4 OR BARC or ARC OR DARC) NEAR20 etch\$4	US-PGPUB; USPAT	OR	OFF	2006/05/11 15:07
L3	202	L2 AND ((photo\$resist\$4 OR resist\$4) NEAR20 (organic\$4 OR polymer\$4) NEAR20 (residue\$4 OR by\$1product\$4 OR scum\$4))	US-PGPUB; USPAT	OR	OFF	2006/05/11 15:07
L4	187	L3 AND (poly\$1silicon\$4 OR silicon\$4)	US-PGPUB; USPAT	OR	OFF	2006/05/11 15:06
L5	6788	((216/41,49,51,74,75,79) or (134/1.2) or (438/706,714,719, 722-725)).CCLS.	US-PGPUB; USPAT	OR	OFF	2006/05/11 15:07
L6	45	L4 AND L5	US-PGPUB; USPAT	OR	OFF	2006/05/11 15:07
L7	2018	(anti\$1reflecti\$4 OR BARC or ARC OR DARC) NEAR20 etch\$4	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/05/11 15:07
L8	7	L7 AND ((photo\$resist\$4 OR resist\$4) NEAR20 (organic\$4 OR polymer\$4) NEAR20 (residue\$4 OR by\$1product\$4 OR scum\$4))	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/05/11 15:07

5/11/2006 3:08:54 PM
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